Excitonic Refractive Index Change in High Purity GaAs Modulator at Room Temperature for Optical Fiber Communication Network

Durga Prasad Sapkota, Madhu Sudan Kayastha, Koichi Wakita

Abstract—In this paper, we have compared and analyzed the electroabsorption properties between with and without excitonic effect bulk in high purity GaAs spatial light modulator for optical fiber communication network. The electroabsorption properties such as absorption spectra, change in absorption spectra, change in refractive index and extinction ratio has been calculated. We have also compared the result of absorption spectra and change in absorption spectra with the experimental results and found close agreement with experimental results.

Keywords—Exciton, Refractive index change, Extinction ratio.

I. INTRODUCTION

There has been considerable interest in the electric field dependence of optical properties in GaAs material with excitonic effect. The importance of exciton effects was cleared by Dow and Redfield [1] below and far above the bandgap. For the first time, a clear excitonic absorption peak was measured at room temperature in high purity GaAs [2]. The shift of electroabsorption near the band-gap to the lower energy was experimentally verified [3]. The studies of the advantages of exciton effects in the presence of electric field were increased in recent years. It is also important that the size of changes in refractive index due to electroabsorption is attractive for electro-optic devices. In this paper, we have compared electroabsorption properties with and without exciton effect and verified with experimental result. The change in absorption coefficient, change in refractive index and extinction ratio in the presence of electric field have been calculated.

II. THEORETICAL MODELS

The electroabsorption with exciton band and continuum band transition including Gaussian function and Sommerfield factor at RT can be defined [4]

\[ \alpha(x) = G(x) + \alpha_c(x) \]

\[ \alpha_c(x) = f \delta(x) + S(x) \]

\[ x = \frac{\hbar c - E_{ex}}{\hbar \Gamma} \]

where is Planck constant, e is electron charge, n is refractive index, \( m \) is free electron mass, c is speed of light in vacuum, d is thickness of active layer, f is oscillator strength, \( \delta(x) \) is delta function, \( G(x) \) is Gaussian function, \( Q_x \) is exciton quenching factor, \( S(x) \) is Sommerfeld factor, \( f \) is oscillator strength, \( M_{\text{ev}} \) is dipole matrix element, \( E_{ex} = E_0 + \Delta E \) is exciton energy and \( \alpha_0 \) is bohradius.

The exciton peak shift can be written for low field and high field, respectively as [4]:

\[ \Delta E = -6 \times 10^{-3} \frac{\hbar}{\hbar_f^2} \]

\[ \Delta E = -19 \times 10^{-3} \frac{\hbar}{\hbar_f^2} \]

The half-width at half maximum of exciton \( \Gamma \) can be defined as [4].

\[ \hbar \Gamma = 26 \times 6.5 \times 10^{-3} \frac{1}{f} e^{-10/3f} \]

The relationship between change in absorption and refractive index change near the absorption edge for excitonic transitions is given by the Kramers-Kronigdispersion relation [5].

\[ \Delta n = \frac{c}{\pi} \int_0^{\infty} \frac{\Delta \alpha \omega}{\omega^2 - \omega_0^2} \]

where \( c \) is velocity of light, \( E \) is transition energy \( \hbar \omega \) is photon energy.

III. RESULT AND DISCUSSION

For the simulation, the software based on Mathcad has been used in this work. The absorption coefficient with Coulomb
interaction including exciton and continuum band at room
temperature as well as associated with electric field in the
presence of both exciton and continuum broadening has been
considered in this work.

In Fig. 1, we have compared the structure of
electroabsorption modulators which are waveguide type and
surface-normal type. The waveguide has many disadvantages
such as difficult to fabricate a 2D array, poor misalignment
tolerance, and large size and fabrication complication whereas
surface-normal type has also disadvantage such as short
optical path length.

![Transmitted light (I_T)](image)

![Incident light (I_i)](image)

Waveguide type

Surface-normal type

(Γ = 0.3)

(Γ = 1)

Fig. 1 Structure of electroabsorption modulator

![Electric field distribution in high purity and low purity GaAs at two different voltages](image)

The electric field distribution between high purity and low
purity GaAs has been compared. Fig. 2 shows that the electric
field at high purity GaAs has distributed widely than that of
low purity GaAs.

Fig. 3 shows the absorption spectra with excitonic effects
for high purity GaAs with 5μm thickness with impurity
concentration of \(1 \times 10^{14} \text{ cm}^{-3}\) at various electric fields. The
linewidth broadening of exciton and stark energy shift with
excitonic effect due to external applied voltage have been
included in our calculation based on (8), (9), and (10)
respectively. The linewidth broadening due to continuum
band absorption is also included. In Fig. 3, the absorption
spectra after exciton peak in experimental result at lower
energy shows higher value than that of our result because this
may be due to the reflection loss, coupling loss and substrate
loss. The excitonic peak remains stable toward the lower
energy having large red shift even at electric field of 70 kV/cm
indicating that the electric field is uniform inside the active
layer, which implies very high purity in active region. In the
Fig. 3, the calculated absorption spectra without exciton effect
at two different electric field is also shown.

![Absorption spectra of theretical and experimental at two different electric field](image)

![Electroabsorption change of measured and theoretical results with and without exciton](image)

Our numerical simulation discussed for GaAs bulk material
with the thickness and carrier concentration of 5 μm of
\(1 \times 10^{14} \text{ cm}^{-3}\), respectively as shown in Table I. The material
dependence parameters such as reduced mass of electron and
hole (\(\mu\)) and bandgap \(E_g\) is taken as 0.069 \(m_0\) and 1.425 eV
respectively. The change in absorption coefficient as a function
of photon energy with and without exciton absorption at the
electric field of 70 kV/cm as well as measured absorption coefficient with exciton at the same electric field in shown Fig. 4. It is shown that the calculated change in absorption coefficient has closed agreement with the experimental ones. Our calculation shows that the change in absorption coefficient with exciton and without exciton was compared at photon energy of 1.406 eV. It is found that the change in absorption coefficient is 2.19 times higher with exciton effect than that of without exciton effect.

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The basic method of our simulation is used for the calculation of refractive index change by using Kramers-Kronig dispersion relation. The change in refractive index has been calculated from the absorption coefficient change association with the applied electric field of 70 kV/cm below the bandgap as shown in Fig. 6. The refractive index change with exciton absorption is estimated to be about 2.08 times higher than that of without exciton effect at photon energy of 1.406 eV.

Fig. 7 shows the extinction ratio as a function of photon energy with and without exciton effect. The extinction ratio with and without exciton effect has been calculated based on the relation $10\log(e^\Delta a d)$, where, $\Delta a$ is the change in absorption coefficient and $d$ is the thickness of active layer. The extinction ratio is same up to photon energy of 1.38 eV and the gap between the extinction ratio with and without exciton effect is increased up to 1.41 eV. The extinction ratio is higher with exciton effect than without exciton effect in the range of 1.38 eV to 1.41 eV and it is 2.06 times higher at photon energy of 1.406 eV. At this photon energy, the extinction ratio is estimated to be 13dB at 70 kV/cm.

### IV. CONCLUSION

In conclusion, we have calculated the change in absorption coefficient, change in refractive index and extinction ratio associated with exciton effect at two different electric fields. We obtained the good agreement with experimental results. We have concluded that the performance characteristics such as refractive index change, extinction ratio of bulk high purity GaAs layer for spatial light modulator can be enhanced with exciton effect. It is found that the change in absorption coefficient is almost double with exciton effect which consequently doubles the change in refractive index in exciton effect than in without exciton. The refractive change in this work is reached nearly to the refractive change of quantum
well structured external modulator. The extinction ratio has been estimated to be about 2.06 times higher with exciton effect than without.

REFERENCES


Durga Prasad Sapkota was born in Sept. 1972. He received his M. Sc. Degree in Mathematics from Tribhuvan University, Kathmandu, Nepal, in 1998. He received Ph.D. degree from the Graduate School of Electrical and Electronics Engineering of Chubu University, Aichi, Japan in 2012. His research interests are related with multiple quantum well and bulk optoelectronic devices for optical fiber communication. He joined Nepal Telecom in 1994 and has continued till this date as a responsibility of research task in research and development of Nepal Telecom.

M. S. Kayastha was born in Jan 1980. He received his B.E degree in Electronics and Communication Engineering from Pokhara Engineering College, Pokhara, Nepal in 2004 and his M.E and Ph. D degree from Chubu University, Aichi, Japan in 2007 and 2011, respectively. He had been engaged in research and development of high efficiency spatial modulator using high purity GaAs by liquid phase epitaxy method. He had also been engaged in synthesis and characterization of graphene film by ME-SWP-CVD and thermal CVD. He is a member of Nepal Engineers Association (NEA) and Nepal Engineering Council (NEC). He joined Kathford Int’l College of Engineering and Management on June, 2014 as a Senior lecturer and Head of Department in Department of Computer and Electronics & Communication Engineering. He is also affiliated to Kathmandu Institute of Applied Science.

Koichi Wakita received his B. S. degree in Electronics Engineering from the Nagoya Institute of Technology in 1968 and his M. S. and Dr. Eng. degree from Nagoya University in 1970 and 1976, respectively. In 1973, he joined NTT Electrical Communication Laboratories, Japan. He had been engaged in research and development of semiconductor lasers and multiple quantum well optical modulators for the optical fiber communication. In 1997, he joined the Department of Electronics and Information Engineering in Chubu University, Aichi, Japan, as a professor. He is a member of the IEICE of Japan, the Institute of Electrical Engineers of Japan, and the Japan Society of Applied Physics.